

BEST AVAILABLE COPY

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 2000-303180
 (43)Date of publication of application : 31.10.2000

(51)Int.Cl.

C23C 16/44
 B05B 1/14
 H01L 21/285

(21)Application number : 11-110147

(71)Applicant : HITACHI LTD
 TOKYO ELECTRON LTD

(22)Date of filing : 16.04.1999

(72)Inventor : KAJIYAMA MORIO
 NAKATSUKA SAKAE
 AEBA YASUSHI

(54) PROCESSOR

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a processor in which an unnecessary film is difficult to deposit, but difficult to be peeled, the cleaning interval can be prolonged, and generation of particles can be suppressed by applying a special treatment to a surface of a metal member including a processing container.

SOLUTION: In a processor 14 to process a work W in a specified manner by placing the work W on a placement base 22 in an evacuative processing container 16, and feeding a processing gas from a shower head part 74 provided on a ceiling part of the processing container 16, organic mechanical-chemical polishing, blasting and anodizing are successively executed on the surfaces of aluminum members 16, 74 used for the processor. An unnecessary film is difficult to deposit, but difficult to be peeled, and the cleaning interval can be prolonged thereby.

